

filed 7/25/03

## ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

### Title of Invention

SYSTEM AND METHOD OF ALTERING A VERY SMALL  
SURFACE AREA BY MULTIPLE CHANNEL PROBE

Application Number : 10/ 604,486  
Confirmation Number:  
First Named Applicant: Hendrik Hamann  
Attorney Docket Number: FIS920020170US1  
Art Unit: 1765  
Examiner: Alanko  
Search string: ( 5865978 or 6002471 or 4880496 or 6078055 ).pn

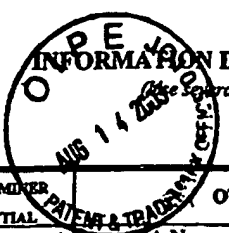


### US Patent Documents

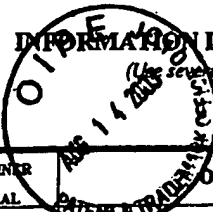
Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
AKC	1	5865978	1999-02-02	Cohen		205	118
	2	6002471	1999-12-14	Quake		356	73
	3	4880496	1989-11-14	Nebenzahl, et al.		216	93
	4	6078055	2000-06-20	Bridger, et al.	AKC	250	442.2

### Signature

Examiner Name	Date
Alanko	6/20/05

<div style="text-align: center;">  <p>filed 8/14/03</p> </div>		Docket Number (Optional) <b>FIS920020170US1</b>	Application Number <b>10/604,486</b>
		Applicant(s) <b>Hendrik F. Hamann et al.</b>	
		Filing Date <b>07/25/2003</b>	Group Art Unit <b>1765</b>
<b>*EXAMINER INITIAL</b> <b>OTHER DOCUMENTS</b> (Including Author, Title, Date, Pertinent Pages, Etc.)			
<div style="text-align: center;">  </div>	<div style="text-align: center;">  </div>	A Nanoplotter with Both Parallel and Serial Writing Capabilities, Seunghun Hong and Chad A. Mirkin, Science Magazine, Vol. 288, June 9, 2000, pp 1808-1811. ✓	
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EXAMINER <i>Quita Glauco</i>		DATE CONSIDERED <i>6/20/05</i>	
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			

<b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary) 		Docket Number (Optional) <b>FIS920020170US1</b>	Application Number <b>10/604,486</b>
		Applicant(s) <b>Hendrik F. Hamann et al.</b>	
Filing Date <b>07/25/2003</b>		Group Art Unit	
*EXAMINER INITIAL	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
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EXAMINER <i>Adrita Shankar</i>		DATE CONSIDERED <i>6/20/05</i>	
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			

# INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)

FIS9200201.7QUS1

Application Number

10/604,48'6

Applicant(s)

Hendrik F. Hamann et al.

Filing Date

07/25/2003

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INITIAL

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EXAMINER

Quinta Hamann

DATE CONSIDERED

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